

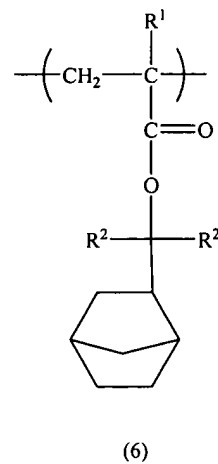
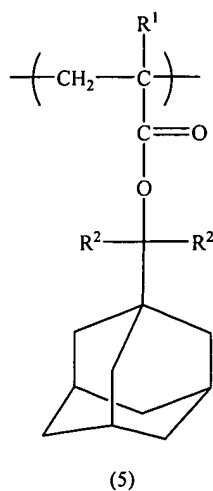
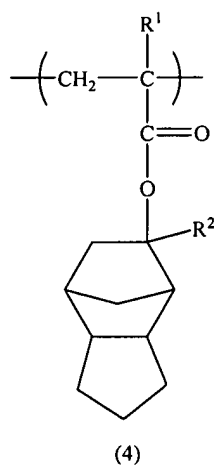
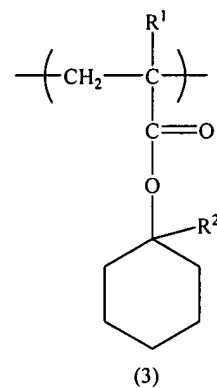
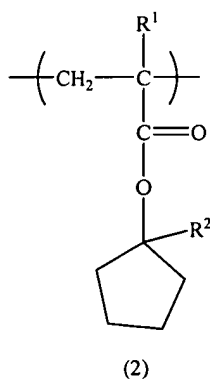
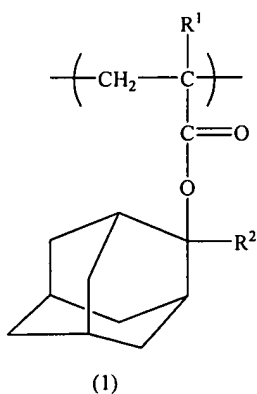
Amendments to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

1. (Previously Presented) A radiation-sensitive resin composition comprising:

(A) a resin comprising a copolymer consisting of methacrylate or acrylate recurring units, wherein the copolymer comprises at least two recurring units of the following formulas (1) - (6),



wherein R¹ represents a hydrogen atom or methyl group and R² represents a substituted or unsubstituted alkyl group having 1-4 carbon atoms, two or more R² groups that may be

present being either the same or different, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator;

wherein the copolymer comprises a combination of recurring units selected from the group consisting of:

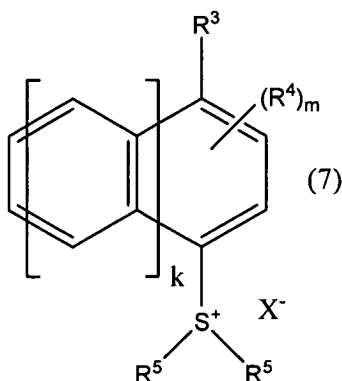
- a recurring unit of formula (1) and a recurring unit of formula (2);
- a recurring unit of formula (1) and a recurring unit of formula (3);
- a recurring unit of formula (1) and a recurring unit of formula (4);
- a recurring unit of formula (1) and a recurring unit of formula (5);
- a recurring unit of formula (1) and a recurring unit of formula (6);
- a first recurring unit of formula (2) and a second recurring unit of formula (2);
- a recurring unit of formula (2) and a recurring unit of formula (3);
- a recurring unit of formula (2) and a recurring unit of formula (4);
- a recurring unit of formula (2) and a recurring unit of formula (5);
- a recurring unit of formula (2) and a recurring unit of formula (6);
- a first recurring unit of formula (3) and a second recurring unit of formula (3);
- a recurring unit of formula (3) and a recurring unit of formula (4);
- a recurring unit of formula (3) and a recurring unit of formula (5);
- a recurring unit of formula (3) and a recurring unit of formula (6);
- a first recurring unit of formula (4) and a second recurring unit of formula (4);
- a recurring unit of formula (4) and a recurring unit of formula (5);
- a recurring unit of formula (4) and a recurring unit of formula (6);

a first recurring unit of formula (5) and a second recurring unit of formula (5);

a recurring unit of formula (5) and a recurring unit of formula (6); and

a first recurring unit of formula (6) and a second recurring unit of formula (6).

2. (Previously Presented) The radiation-sensitive resin composition according to Claim 1, wherein the photoacid generator (B) is compound shown by the formula (7),



wherein R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxycarbonyl group having 2 - 11 carbon atoms, R^4 represents a linear or branched alkyl group having 1 - 10 carbon atoms, R^5 individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms, k is an integer of 0 to 2, X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ (wherein R^6 represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 0 to 10.

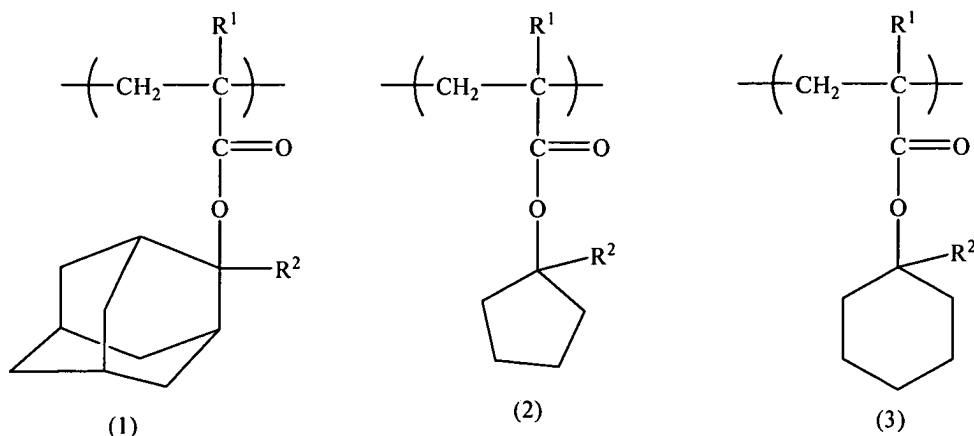
3. (Original) The radiation-sensitive resin composition according to Claim 1, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent

comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

4-6. (Canceled).

7. (Currently Amended) A radiation-sensitive resin composition comprising,

(A) a resin comprising a copolymer consisting of methacrylate or acrylate recurring units, wherein the copolymer comprises ~~at least one~~ a first recurring unit of the following formulas (1) - (3),



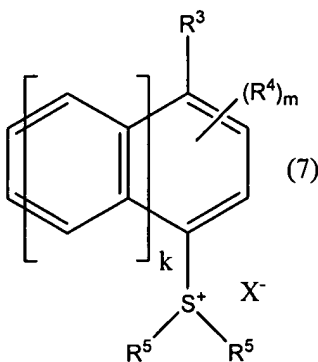
wherein R^1 represents a hydrogen atom or methyl group and R^2 is a methyl group, and at ~~least one~~ a second recurring unit of the above formulas (1) - (3), wherein R^1 represents a hydrogen atom or methyl group and R^2 represents a substituted or unsubstituted alkyl group having 1 - 4 carbon atoms, excluding a methyl group, two or more R^2 groups that may be present being either the same or different, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator;

wherein the copolymer comprises a combination of recurring units selected from the group consisting of:

- a recurring unit of formula (1) and a recurring unit of formula (2);
- a recurring unit of formula (1) and a recurring unit of formula (3);
- a first recurring unit of formula (2) and a second recurring unit of formula (2);
- a recurring unit of formula (2) and a recurring unit of formula (3); and
- a first recurring unit of formula (3) and a second recurring unit of formula (3).

8. (Previously Presented) The radiation-sensitive resin composition according to Claim 7, wherein the photoacid generator (B) is the compound shown by the formula (7),



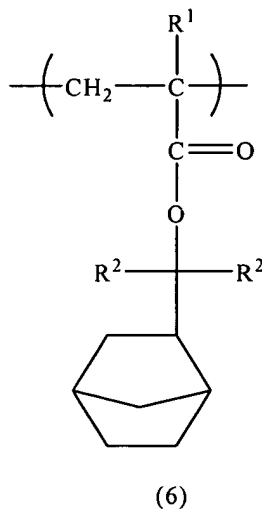
wherein R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxy carbonyl group having 2 - 11 carbon atoms, R^4 represents a linear or branched alkyl group having 1 - 10 carbon atoms, R^5 individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms, k is an integer of 0 to 2, X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ (wherein

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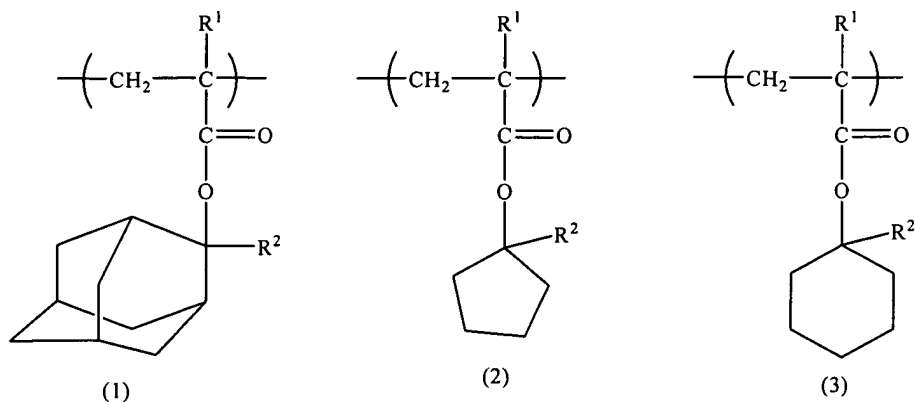
R^6 represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 0 to 10.

9. (Previously Presented) The radiation-sensitive resin composition according to Claim 7, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

10. (Previously Presented) A radiation-sensitive resin composition comprising, (A) a resin comprising at least one recurring unit of the following formula (6),



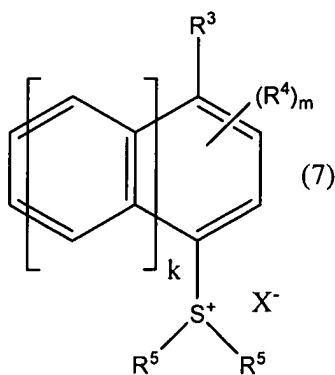
wherein R^2 is a methyl group, and at least one recurring unit selected from the group consisting of the recurring units of the formulas (1) - (3),



wherein R^1 represents a hydrogen atom or methyl group and R^2 is a methyl group, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid, and

(B) a photoacid generator.

11. (Previously Presented) The radiation-sensitive resin composition according to Claim 10, wherein the photoacid generator (B) is the compound shown by the formula (7),



wherein R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxycarbonyl group having 2 - 11 carbon atoms, R^4 represents a

linear or branched alkyl group having 1 - 10 carbon atoms, R^5 individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms, k is an integer of 0 to 2, X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ (wherein R^6 represents a fluoroine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10), and m is an integer of 0 to 10.

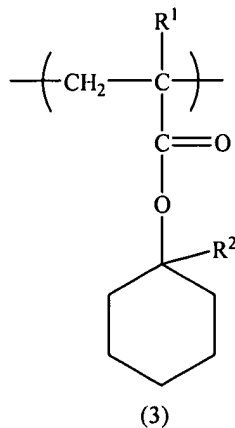
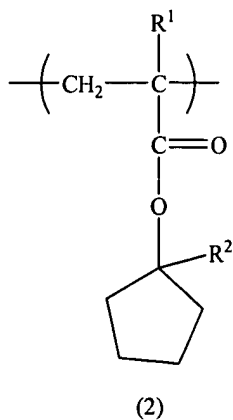
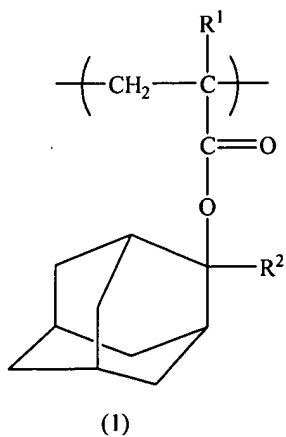
12. (Previously Presented) The radiation-sensitive resin composition according to Claim 10, wherein the resin (A) and the photoacid generator (B) are dissolved in a solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

13-14. (Canceled).

15. (Currently Amended) A radiation-sensitive resin composition comprising:

(A) a resin comprising ~~at least one~~ a first recurring unit of the following formulas

(1) - (3),

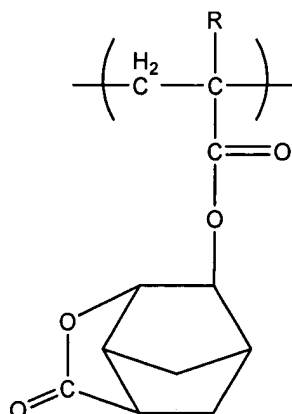


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wherein R^1 represents a hydrogen atom or methyl group and R^2 is a methyl group, and at least one a second recurring unit of the above formulas (1) - (3), wherein R^1 represents a hydrogen atom or methyl group and R^2 represents a substituted or unsubstituted alkyl group having 1 - 4 carbon atoms, excluding a methyl group, two or more R^2 groups that may be present being either the same or different, in the total amount of 5 - 70 mol %, but each in the amount of 1 - 49 mol %, the resin being insoluble or scarcely soluble in alkali, but becoming easily soluble in alkali by the action of an acid; and

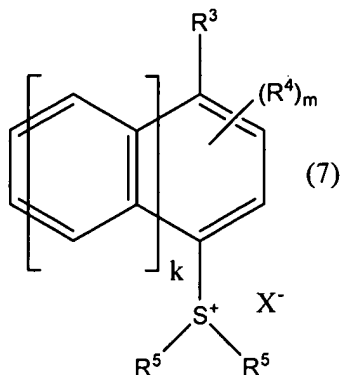
(B) a photoacid generator;

wherein the resin further comprises the recurring unit shown by the following formula:



wherein R represents a hydrogen atom or a methyl group.

16. (Currently Amended) The radiation-sensitive resin composition according to Claim [[13]] 15, wherein the photoacid generator (B) is compound shown by the formula (7),



wherein:

R^3 represents a hydrogen atom, hydroxyl group, linear or branched alkyl group having 1 - 10 carbon atoms, linear or branched alkoxy group having 1 - 10 carbon atoms, or linear or branched alkoxy carbonyl group having 2 - 11 carbon atoms;

R^4 represents a linear or branched alkyl group having 1 - 10 carbon atoms;

R^5 individually represents a linear or branched alkyl group having 1 - 10 carbon atoms, substituted or unsubstituted phenyl group, or substituted or unsubstituted naphthyl group, or two R^5 groups bond to form a substituted or unsubstituted divalent group having 2 - 10 carbon atoms;

k is an integer of 0 to 2;

X^- represents an anion represented by the formula $R^6C_nF_{2n}SO_3^-$ wherein R^6 represents a fluorine atom or substituted or unsubstituted monovalent hydrocarbon group and n is an integer of 1 to 10; and

m is an integer of 0 to 10.

17. (Currently Amended) The radiation-sensitive resin composition according to Claim [[13]] 15, wherein the resin (A) and the photoacid generator (B) are dissolved in a

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solvent comprising at least one compound selected from the group consisting of propylene glycol mono-methyl ether acetate, 2-heptanone, and cyclohexanone.

18-19. (Canceled).